

# **ECR Ion Source Operations**

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# Outline

- 1. 88-Inch Facility Layout
- 2. Intro to ECRs
- 3. Cocktail Beams
- 4. Availability & Reliability
- 5. Resources to Support Chip Testing and SHE

AECR-U aluminum plasma chamber

#### **Cyclotron Facility Layout**

The 88-Inch Cyclotron is fed by three ECR ion sources: ECR, AECR-U, and VENUS.



# ECR Ion Source Physics

ECR: Electron Cyclotron Resonance

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#### ECR's at the 88-Inch



## ECR's at the 88-Inch

ECR 1983 Max B-Field: 0.4T Frequencies: 6.4GHz Max Power: 0.6kW	AECR-U 1996 Max B-Field: 1.7T Frequencies: 10, 14GHz Max Power: 2.6kW	VENUS 2004, 2008 for operations Max B-Field: 4.0T (superconducting) Frequencies: 18, 28GHz Max Power: 12kW	MARS (Dan's Talk)

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#### **Beams Produced/Accelerated**



#### What Makes a Good ECR Source?



#### **VENUS ECR Ion Source**

- Currently one of the most powerful ECR ion sources in the world •
- Exploring limits of ECR ion sources through **R&D** •



#### **Cocktail Beams Development**

Development of new cocktail ions using VENUS to increase LET and range underway <sup>124</sup>Xe<sup>43+</sup> in 16MeV cocktail: extends LET from 25 to 50MeV/(mg/cm<sup>2</sup>) → now regularly used <sup>197</sup>Au<sup>52+</sup> in 10MeV cocktail: extends LET from 59 to 86MeV/(mg/cm<sup>2</sup>) → now regularly used <sup>124</sup>Xe<sup>47+</sup> in 20MeV cocktail: also now regularly used!

20MeV/u	M/Q	Production Method	<u>LET</u> (MeV/(mg/ <u>cm²))</u>	<u>RANGE</u> <u>(μm)</u>
<sup>20</sup> Ne <sup>8+</sup>	2.50	GAS	1.92	548.5
<sup>27</sup> Al <sup>11+</sup>	2.45	GAS	3.25	463.9
<sup>78</sup> Kr <sup>32+</sup>	2.44	GAS	20.9	243.3
<sup>89</sup> Y <sup>36+</sup>	2.47	Sputter Probe	24.2	244.9
<sup>109</sup> Ag <sup>44+</sup>	2.48	Sputter Probe	33.3	226.8
<sup>124</sup> Xe <sup>47+</sup>	2.64	GAS	45.4	193.8

Why the need for 20MeV/u cocktail?

- increasing beam energy allows for deeper penetration into parts
- Layers on chips are increasing in thickness

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Development for higher energy beams to use for testing in air if this is requested...ex: 25MeV/u<sup>78</sup>Kr<sup>34+</sup>



### ECR Ion Source Reliability & Availability

Reliability	Fail time due to ECRs since 2/2/2017 is 13.5 hrs! However, this doesn't mean all ions were always available! AECR-U & VENUS not one-to-one replacements for each other.	4 Cryocoolers
Availability	VENUS availability for <u>beam delivery increased</u> : Cryostat Modification Implemented in 2017 and tested successfully in 2019. Additional heaters reduced cryocooler maintenance from ~8 weeks to 1 week!	LHe 4K
	However, <u>beam development time decreased</u> ! Shutdown development time is hampered by LCW outages No cyclotron available during shutdowns	

# Mitigating Risks





plasma

AECR Failure: No sputter probe metals (Ag, Y, Ta, Cu, Tb, Si, V)Sputter probe with multiple metals at VENUSVENUS HiT Oven Failure: unreliable, no spare shaftBuild a spa Oven shaftVENUS Failure: No high charge state Au, Xe, KrBackup to VENUS: 3rd/4th generation ion sourceVENUS Hit Oven Failure: unreliable, no spare shaftBackup to VENUS failure: at AECR with liner, lower intensity and higher consumptionBackup to venus source	r cocktails Increase reliability for SHE Solution Failure & Consequence Solution	Increase reliability f Failure & Consequence
VENUS: Failure:Backup to VENUS:at AECR with liner, lowergenerationNo high charge state Au, Xe,3 <sup>rd</sup> /4 <sup>th</sup> generationintensity and highersourceKrion sourceconsumptionintensity and higher	Putter probe with nultiple metals at /ENUSVENUS Hit Oven Failure: unreliable, no spare shaftBuild a spare Hit Oven shaftVENUS Failure: NUS Failure: NUS Failure:Backup to 	<u>CR Failure</u> : sputter probe metals (Ag, a, Cu, Tb, Si, V)
	Low temperature oven run Backup to VENUS:VENUS: 3ra/4th generationat AECR with liner, lower intensity and higher consumptiongeneration ion source	<u>NUS Failure</u> : high charge state Au, Xe,
VENUS high intensity runs: Difficult to run high charge state cocktails afterBackup to VENUS: 3rd/4th generation 	Backup to VENUS: grd/4 <sup>th</sup> generation on source	<u>NUS high intensity runs</u> : ficult to run high charge te cocktails after

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### Source Use



### Conclusions

- To fulfill the needs of the chip testing and research communities, development of VENUS continues
- With the regular use of VENUS for beam production we have less time for R&D
- R&D is not only needed to develop 4<sup>th</sup> generation ECRs but also to develop beams for chip testing and intense beams